

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

**ATTORNEY DOCKET NO. 025311-0111**

Applicant: Tetsuro HANAWA

Title: PROJECTION ALIGNER, EXPOSING METHOD AND  
SEMICONDUCTOR DEVICE

Appl. No.: Unassigned

Filing Date: 11/08/2001

Examiner: Unassigned

Art Unit: Unassigned

**PRELIMINARY AMENDMENT**

Commissioner for Patents  
Washington, D.C. 20231

Sir:

Prior to examination of the above-identified application, Applicant respectfully requests that the following amendments be entered into the application:

**IN THE CLAIMS:**

In accordance with 37 C.F.R. §1.121, please substitute for original claims 18 and 20 the following rewritten version of the same claims, as amended. The change is shown explicitly in the attached "Version with Markings to Show Changes Made."

18. (Amended) The projection exposure method according to claim 10, wherein, in said second step, said substrate is irradiated with exposure light of said appropriate intensity by changing an interval between pulse light emissions of said exposure light.

20. (Amended) A semiconductor device fabricated by use of the projection exposure method according to claim 10.

Appl. No. Unassigned

REMARKS

Applicant respectfully requests that the foregoing amendments to Claims 18 and 20 be made prior to examination of the present application.

Respectfully submitted,

November 8, 2001

Date

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**VERSION WITH MARKINGS TO SHOW CHANGES MADE**

18. (Amended) The projection exposure method [as claimed in any one of claims 10 to 16] according to claim 10, wherein, in said second step, said substrate is irradiated with exposure light of said appropriate intensity by changing an interval between pulse light emissions of said exposure light.

20. (Amended) A semiconductor device fabricated by use of the projection exposure method according to claim[s] 10.